

Notice of References Cited	Application/Control No. 10/719,083	Applicant(s)/Patent Under Reexamination HWANG ET AL.	
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	V	Shibata et al. of Material and Process Development of Tri-level Resist System in KrF and ArF Lithography [Proc. SPIE Vol. 4690, July 2002, Advances in Resist Technology and Processing XIX;
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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